

# SEM ADC

## (Auto Defect Classification)



**How it improves the Cost of Ownership  
without Risk of Yield Loss**

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# SEM ADC (Auto Defect Classification)

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# 1. Introduction

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- ❑ ITRS (International Technology Roadmap for Semiconductors) requires SEM ADC classification capability for 10-15 defect types with 90% accuracy and 90% purity at 720 DPH (defects per hour).
- ❑ Practically, redetection defect size is limited by resolution and the throughput is limited by physical parameters such as detector sensitivity (S/N) and stage vibration. Improvement in these areas depends on SEM physical and theoretical breakthroughs.

# 1. Introduction (continue)

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- ❑ As a result of complicated semiconductor processes, the typical 15 types of defects can be classified with 85-90% of accuracy by trained operators. However, even the state-of-the-art technology of ADC can not classify 10 types of defects with 85-90% accuracy. It is a question of whether ADC is worth installing or not.
- ❑ Introducing SIC (significant impact class) classification and the real-time yield excursion detection method. The benefit of the cost reduction by ADC was estimated.

# 1. Introduction (continue)

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## □ Formula for Evaluation

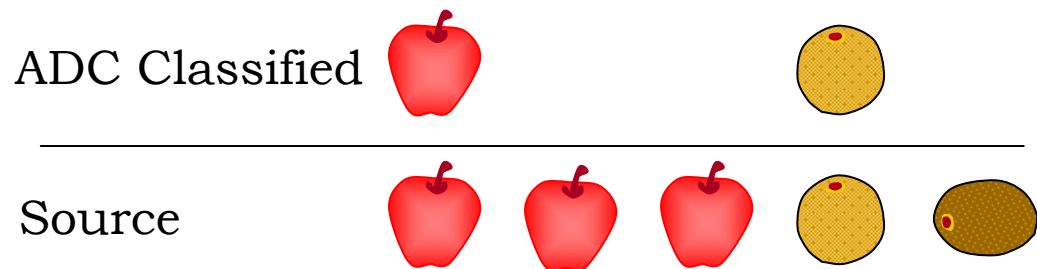
$$Purity = \frac{\textit{the number of defects which human agrees}}{\textit{the number of defects which ADC classified}} \dots\dots\dots(1)$$

$$Accuracy = \frac{\textit{the number of defects which ADC agrees}}{\textit{the number of defects which human classified}} \dots\dots(2)$$

# 1. Introduction (continue)

## □ Purity is important for SPC (Statistical Process Control)

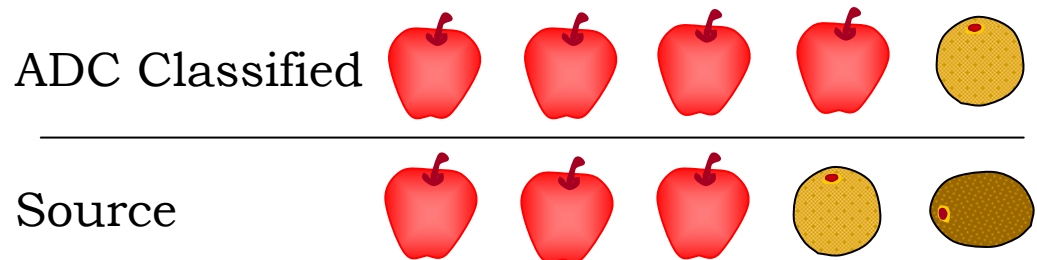
- Purity: I never tell a lie.



Apple purity:

$$\frac{\text{Correct} = 1}{\text{ADC Classified} = 1} = 100\%$$

- Accuracy: I never miss (apple).



Apple accuracy:

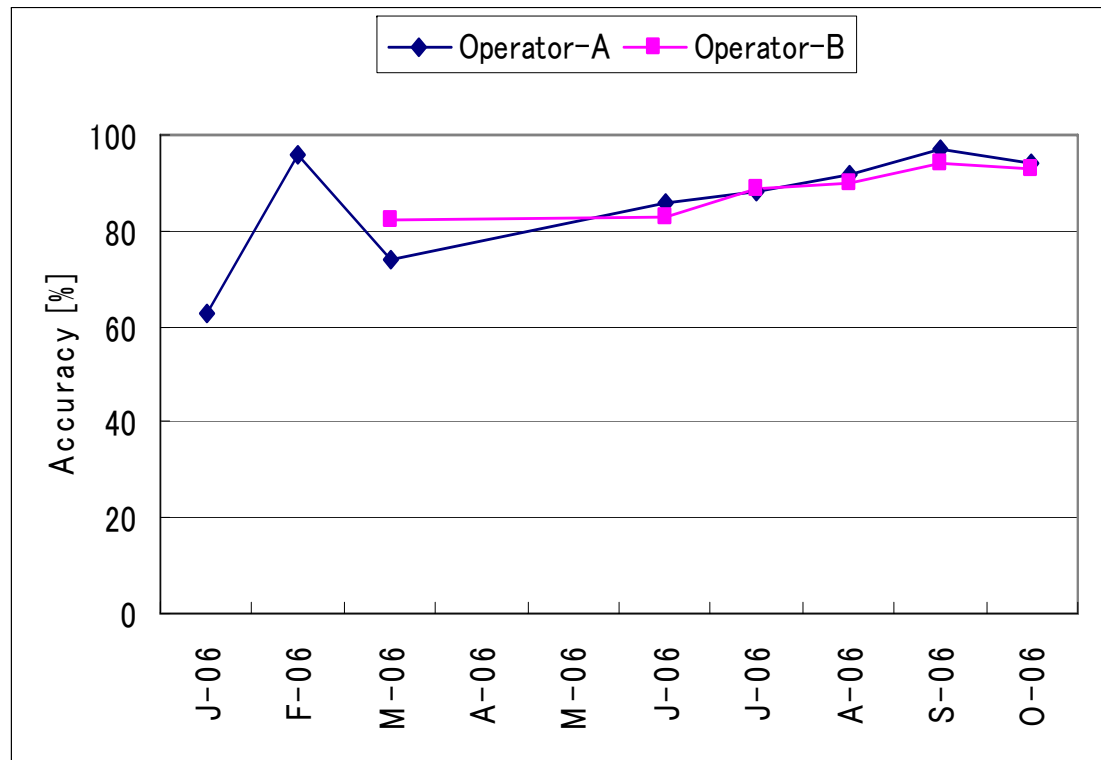
$$\frac{\text{Correct} = 3}{\text{Human Classified} = 3} = 100\%$$

## 2. Concept (Needs)

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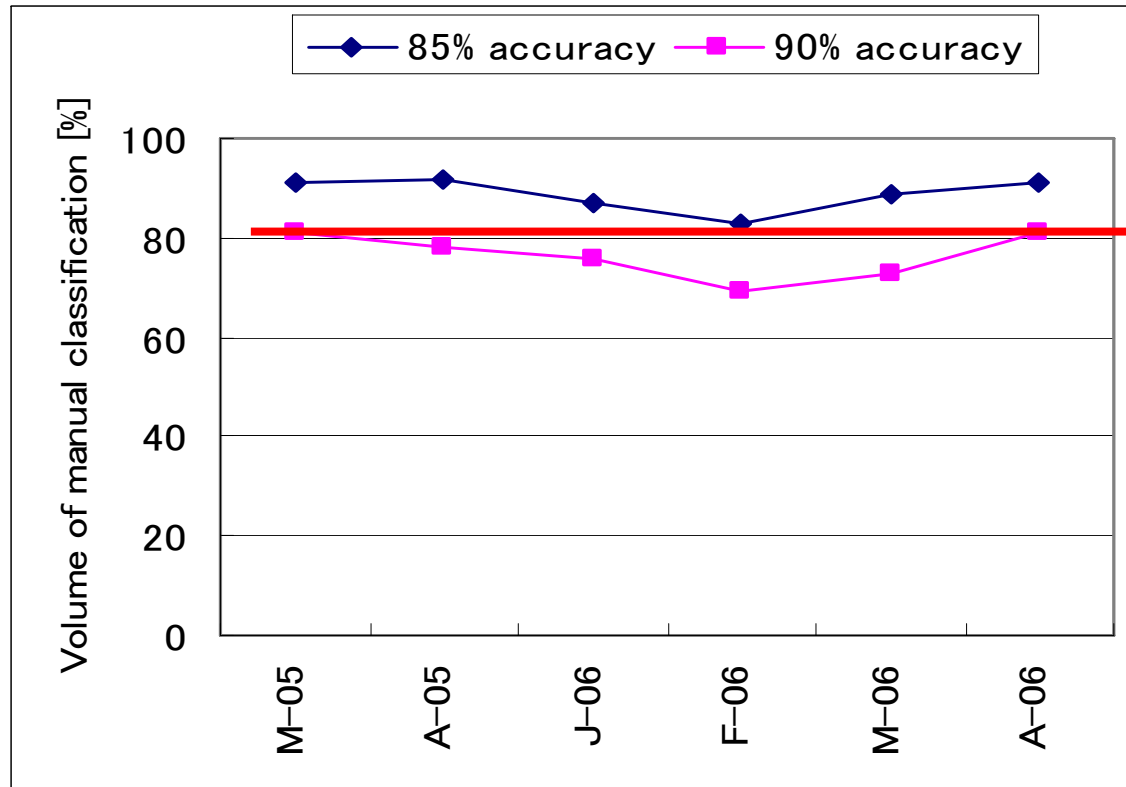
- Needs for Auto Defect Classification (ADC)
  - Importance of Defect Classification
    - Define defect type could predict the end of the line yield impact
    - The correct defect ID could lead the defect source and eliminate further yield impact
  - Human-factor for Manual Defect Classification (MDC)
    - MDC needs highly trained personal with time delay impact
    - Human limitation to classify volume > 90% with high accuracy and purity
  - ADC Improvement Requirements to Use inline
    - ADC must classify > 10 types of defects with 85-90% purity and accuracy
    - ADC needs proper methodology without time delay

# Example of Human-factor: Learning Curve of Classification Accuracy



*6 Months to achieve > 90%*

# Example of Human-factor: The Limitation of Classification-Capability



Human  
Never > 80%

*No one can exceed 80% of volume with 90% match.*

∴

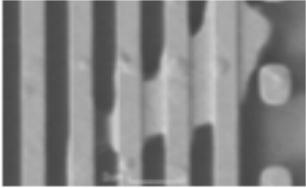
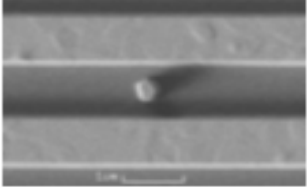
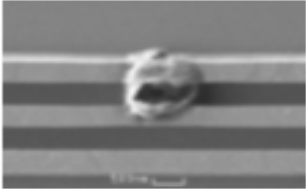
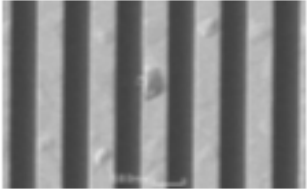
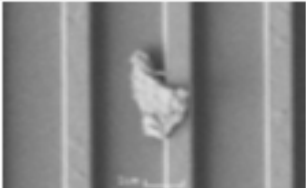
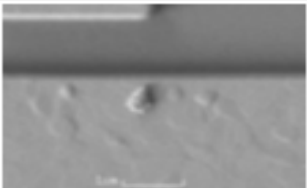
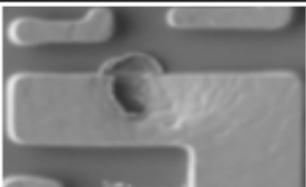

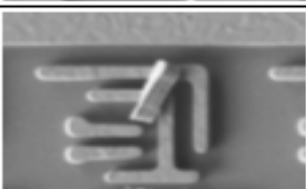
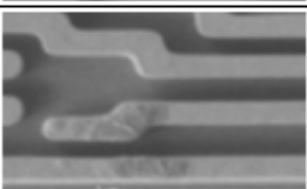
*Accuracy/Purity of Human Classification is <80/90 % Or ~85/85 %.*

## 2. Concept (Solution)

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- ADC Improvements
  - Multiple detectors on the SEM greatly improve ADC accuracy.
  - Advanced ADC algorithm provides accurate output for a few defect types with high accuracy and purity.
  
- Using ADC for Killer Defect Classification
  - ADC can classify the killer types of defects
  - Cost of classification is reduced
  - Yield loss is reduced and the CoO is decreased
    - Excursion will be detected earlier
    - Problem resolution will be tackled before heavy yield loss occurs

# Example of ADC Classification of Killer/Non-Killer Defect Types

Class	Killer (*_K)	Non-Killer (*_NK)
PAT_FLAT		
INFLM_PART		
PARTICLE		
PAT_OTHER		
OTHER		

# 3. Experiment

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## □ Experiment Condition

- SEM Review Tool: JWS7555S
- ADC Architecture: Trainable classification
- Sample: FEOL (front end of line) six layers, and BEOL (back end of line) two layers
- Classes: Total fifty standard classes mapped to user classes and high purity classes are chosen

## □ Killer grouping

- Focus on Killer defects
- All killer classes is classified as “Killer\_X”
- High purity killer classes is classified as “Killer\_Y”

# ADC results of a FEOL layer

(Purity of 5 classes > 85%)

Class Name	ADC												MDC Total	Accuracy[%]	
	PAT_FLAT_K	INFLM_PART_K	Particle_K	Other_K	PAT_FLAT_NK	PAT_OTHER_NK	INFILM_PART_NK	Particle_NK	CANT_FIND	SmallDefect	Exception	Unknown			
MDC	PAT_FLAT_K	193	1	1	99	0	0	0	1	0	0	7	46	348	55.5
	INFLM_PART_K	0	3	0	8	0	0	0	0	0	0	0	0	11	27.3
	Particle_K	1	0	84	206	0	0	0	2	0	0	2	6	301	27.9
	Other_K	1	0	19	201	0	14	3	4	0	0	5	15	262	76.7
	PAT_FLAT_NK	4	0	0	128	71	54	2	37	0	1	10	13	320	22.2
	PAT_OTHER_NK	0	0	0	160	0	731	1	4	0	49	19	11	975	75.0
	INFILM_PART_NK	1	0	0	124	0	0	303	5	0	0	10	5	448	67.6
	Particle_NK	2	0	0	446	6	32	2	110	0	63	15	17	693	15.9
	CANT_FIND	0	0	0	0	0	0	0	0	261	0	0	0	261	100.0
	SmallDefect	0	0	0	0	0	0	0	0	0	4	0	0	4	100.0
	Exception	0	0	0	8	0	0	0	0	0	4	168	6	186	90.3
	Unknown	0	0	0	0	0	0	0	0	0	0	0	0	0	na
	ADC Total	202	4	104	1380	77	831	311	163	261	121	236	119	3809	-
	Purity[%]	95.5	75.0	80.8	14.6	92.2	88.0	97.4	67.5	100.0	3.3	71.2	0.0	-	-

# Killer Grouping of a FEOL layer

(killer\_X: all killers, killer\_Y: high purity killers)

Class Name	ADC				MDC Total	Accuracy[%]	Killer_X Accuracy[%]	Killer_Y Accuracy[%]
	PAT_FLAT_K	INFLM_PART_K	Particle_K	Other_K				
(A) MDC PAT_FLAT_K	193	1	1	99	348	55.5	88.6	90.3
<del>MDC INFLM PART K</del>	0	3	0	8	11	27.3		
Particle_K	1	0	84	206	301	27.9		
Other_K	1	0	19	201	262	76.7		
ADC Total	202	4	104	1380	3809	-		
(B) Purity[%]	95.5	75	80.8	14.6	-	-		
Killer_X Purity[%]	48.3							
Killer_Y Purity[%]	97.7				=(195+4+104)/(202+4+104)			

Killer\_X Purity = #of human agreed killer defects/#of all killer classified defects by ADC = (A)/(B)  
 = (195+4+104+514)/(202+4+104+1380) = 48.3%

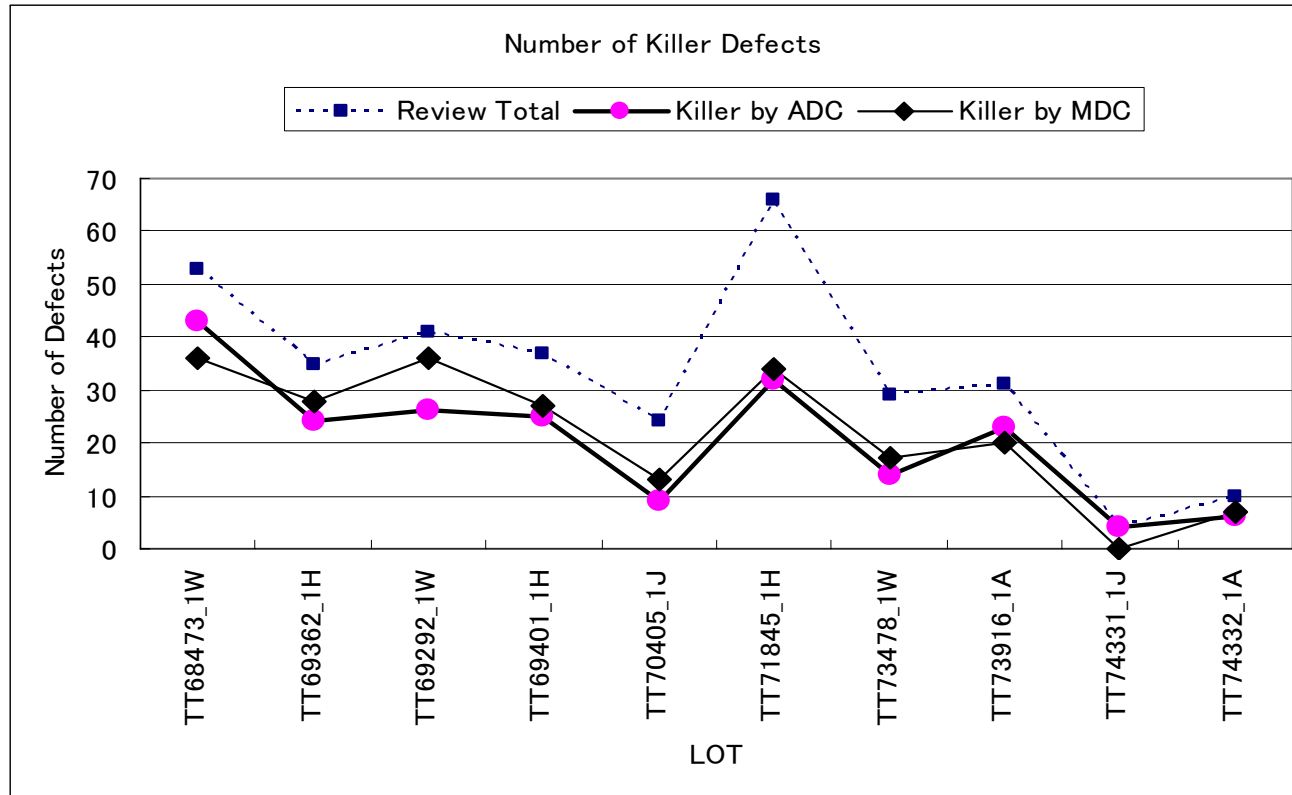
# Killer Grouping Summary (FEOL layer)

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(killer\_X: all killers, killer\_Y: high purity killers)

<b>Class</b>	<b>Purity</b>	<b>Accuracy</b>
<b>Killer_X</b>	<b>48.3%</b>	<b>88.6%</b>
<b>Killer_Y</b>	<b>97.7%</b>	<b>90.3%</b>

# Killer\_X trend



□ *ADC's killer defect classification capability ~ = MDC's*

# 4. Consideration

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- ❑ In order to use killer classes for yield management, both purity and accuracy need to be greater than 85%.
  - Killer\_Y can be used by YMS
  - Killer\_X *CAN'T* be used by YMS
  
- ❑ Introducing Significant Impact Classes (SIC)
  - SIC is the sum of high impact classes (normally killer\_X and non-killer high purity classes).
  - Can SIC be used for yield management?
  
- ❑ ADC Cost Reduction Estimation
  - Can ADC reduce CoO?

# Yield Impact Calculation Formula

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$$I_y = R_{kill} \times F_d$$

$I_y$  Yield impact

$R_{kill}$  Kill ratio of the defect class of the layer

$F_d$  Occurrence frequency of the classified defect

Other formula

$$R_{iadc} = I_{adc} / I_{total} \times 100\%$$

$R_{iadc}$  ADC detection ratio

$I_{adc}$  Impact the ADC can detect

$I_{total}$  Total impact by all defects

$$C_{hp} = N_{hipurity} / N_{adc} \times 100\%$$

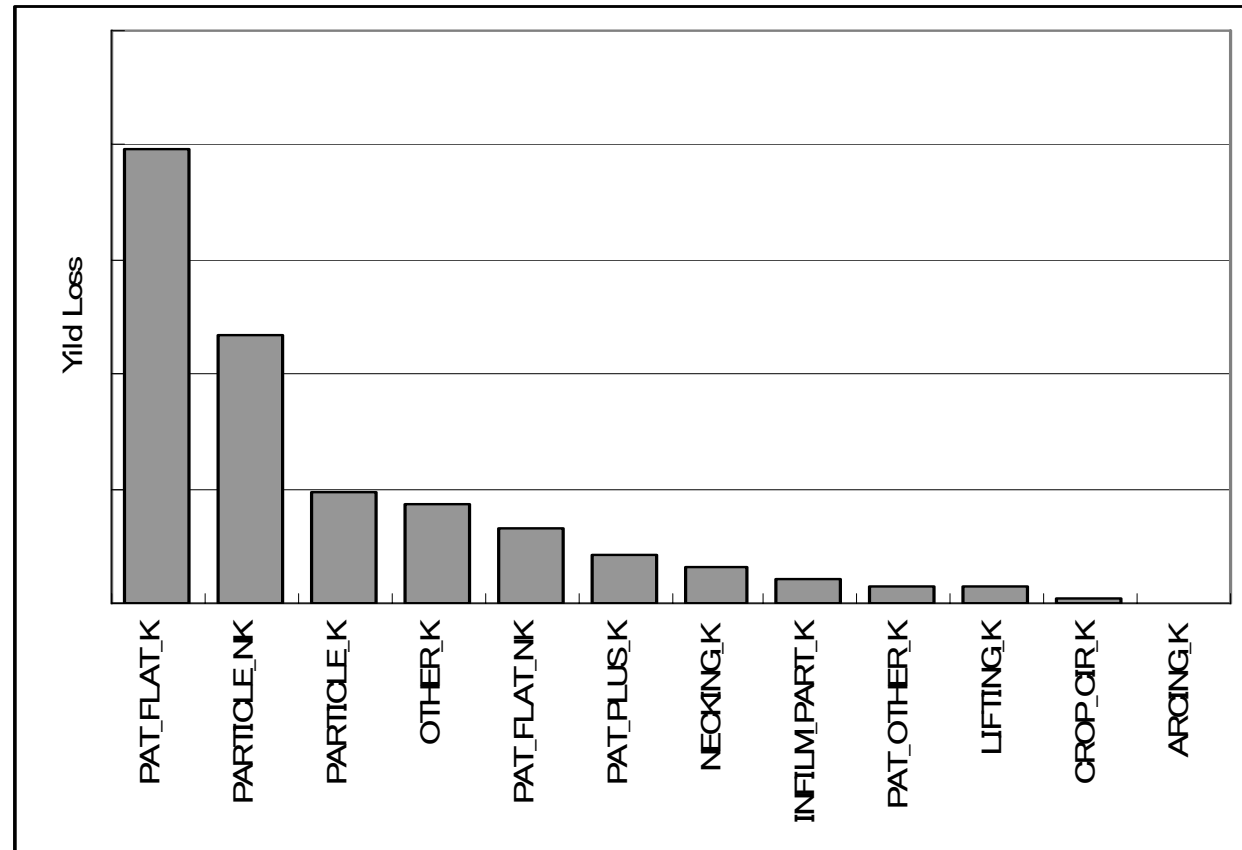
$C_{hp}$  Coverage of high purity classes

$N_{hipurity}$  Number of defect with high purity classes

$N_{adc}$  Number of ADC(ed) all defects

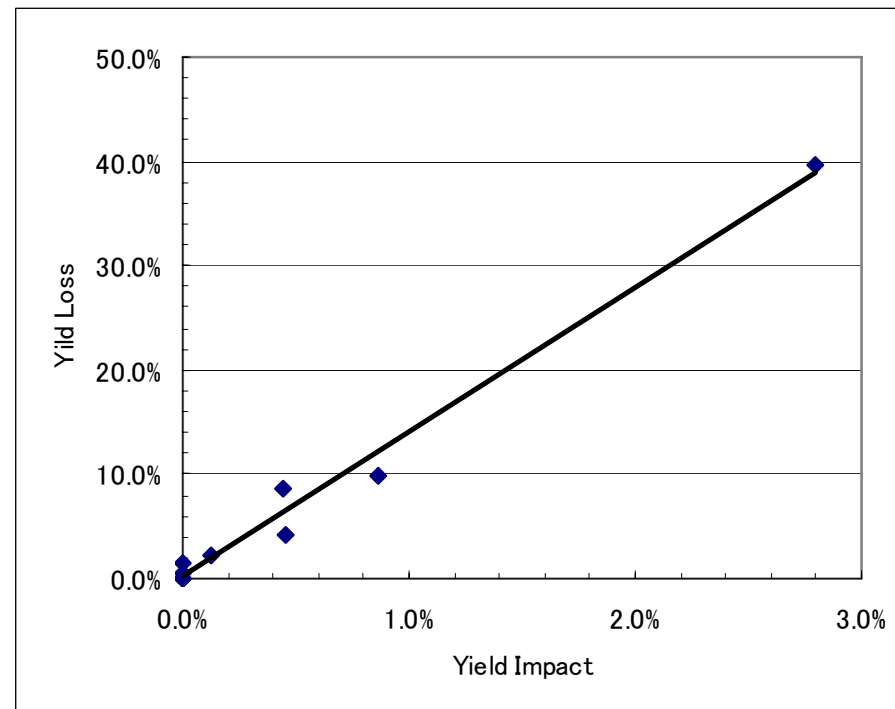
# Yield Loss Pareto of a FEOL Layer

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# Yield Impact vs Yield Loss

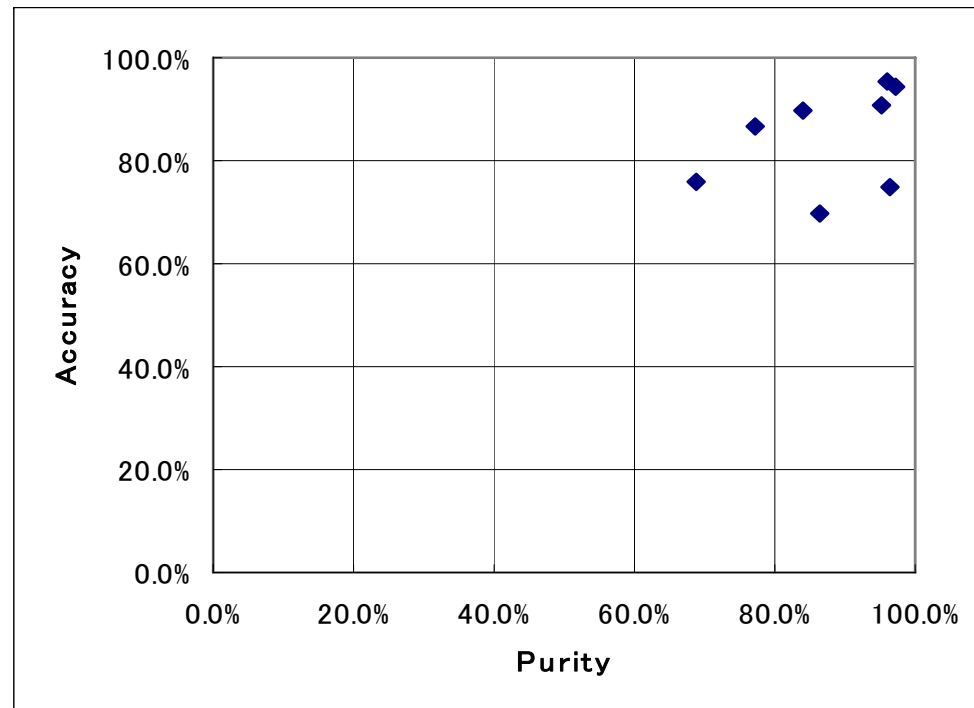
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- *Yield loss has strong correlation with yield impact*

# Result of Significant Impact Classes in Each Layer

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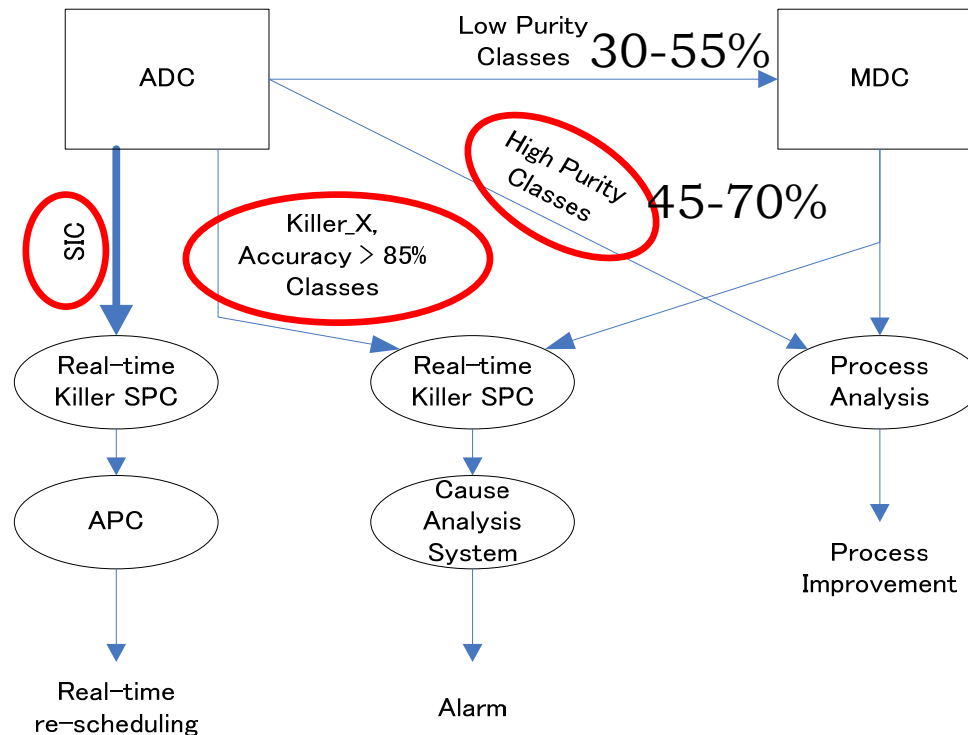
- *Purity and accuracy of SIC > 80%*

# Calculated Yield Impact from ADC Result

Class Layer	Impact [%]					$R_{adc}^i$ Yield Impact Detected Ratio by SIC [%]
	Killer_X	Killer_Y	High Purity Non-killer	SIC	Total	
FEOL	4.7	3.8	2.8	7.5	7.5	100
BEOL	34.1	18.2	0.6	34.7	34.7	100

- *All Impact for the layer was detected by SIC*

# Further ADC Works: Real-time Excursion Control System



- ❑ *All yield loss is detected by SIC*
- ❑ *Excursion is detected at real-time by Killer\_X and high accuracy classes*
- ❑ *High purity classes can be used for process analysis*
- ❑ *MDC work load can be reduced to 30-55%.*

# ADC Cost Reduction Estimation

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$$C_p = N_{product} \times I_y \times N_d \times T_{ddetection} \times P_{chip}$$

- $C_p$  : Cost reduction of the process  
 $N_{product}$  : Number of production wafers per hour of  
manufacture equipment (subject of inspection)  
 $I_y$  : Impact of a defect  
 $N_d$  : Average defects per wafer after fault occurrence  
 $T_{ddetection}$  : Detection lag time caused by manual  
classification [hour]  
 $P_{chip}$  : Price of a chip.

# Cost Reduction for Short Term Excursions

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- If the time taken in the classification and reaction by an engineer were 2 hours, the time of recovery from a failure could be less than 2 hours with ADC. It prevents the large yield loss and reduces the cost significantly.
- When assuming the average detection lag time caused by manual classification is 1 hour, the calculated value for total cost reduction due to ADC is \$105K/year (\*).

(\*) Assumed that 30,000 8-inch wafers are manufactured per month ( $N_{product} = 41.7$  [wafer/hour]). Process equipment fault caused defectivity is estimated at a frequency of one event per month in 2 layers, and assumes 100 defect per wafer increase at the time of the event ( $N_d = 100$  [defect/wafer]). The average detection lag time caused by manual classification is 1 hour ( $T_{ddetection} = 1$  [hour]). When assuming the price of one chip to be \$5 ( $P_{chip} = 5$  [\$]) and average yield impact through layer  $ly$  was 21%, the total cost reduction  $C_p = 41.7$ [wafer/hour] x 21% x 100[defect] x 1 [hour] x 5[\$] x 2[layer] x 12[month] = \$105K/year.

# Cost Reduction for Long Term Excursions

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- Minimization of excursion impact by ADC also shows a tremendous cost saving; > \$800K (\*).

(\* ) Assuming there were one major excursion ( > 300 wafers scrapped), two minor excursions ( > 100 wafers scrapped) during a one year period using in-line monitor inspection with ADC feedback loop, and \$2000/ wafer

## 5. Conclusion

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- ❑ The preliminary result has shown that off-line ADC with SEM images provides significant information and tremendous opportunities for yield improvement and yield prediction.
- ❑ Applying the SIC detection method to ADC, almost all excursions will be detected by SPC with ADC.

## 5. Conclusion (continue)

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- ❑ Rapid feedback will reduce yield loss significantly.
- ❑ ADC will be expanded into the yield improvement world with various types of SEM.
- ❑ It is expected that ADC will be incorporated into APC in the near future.